

MONOLAYER PATTERN FORMING METHOD, ELECTRICALLY CONDUCTIVE FILM PATTERN FORMING METHOD USING PATTERNEDE MONOLAYER AND ELECTRO-OPTIC DEVICE

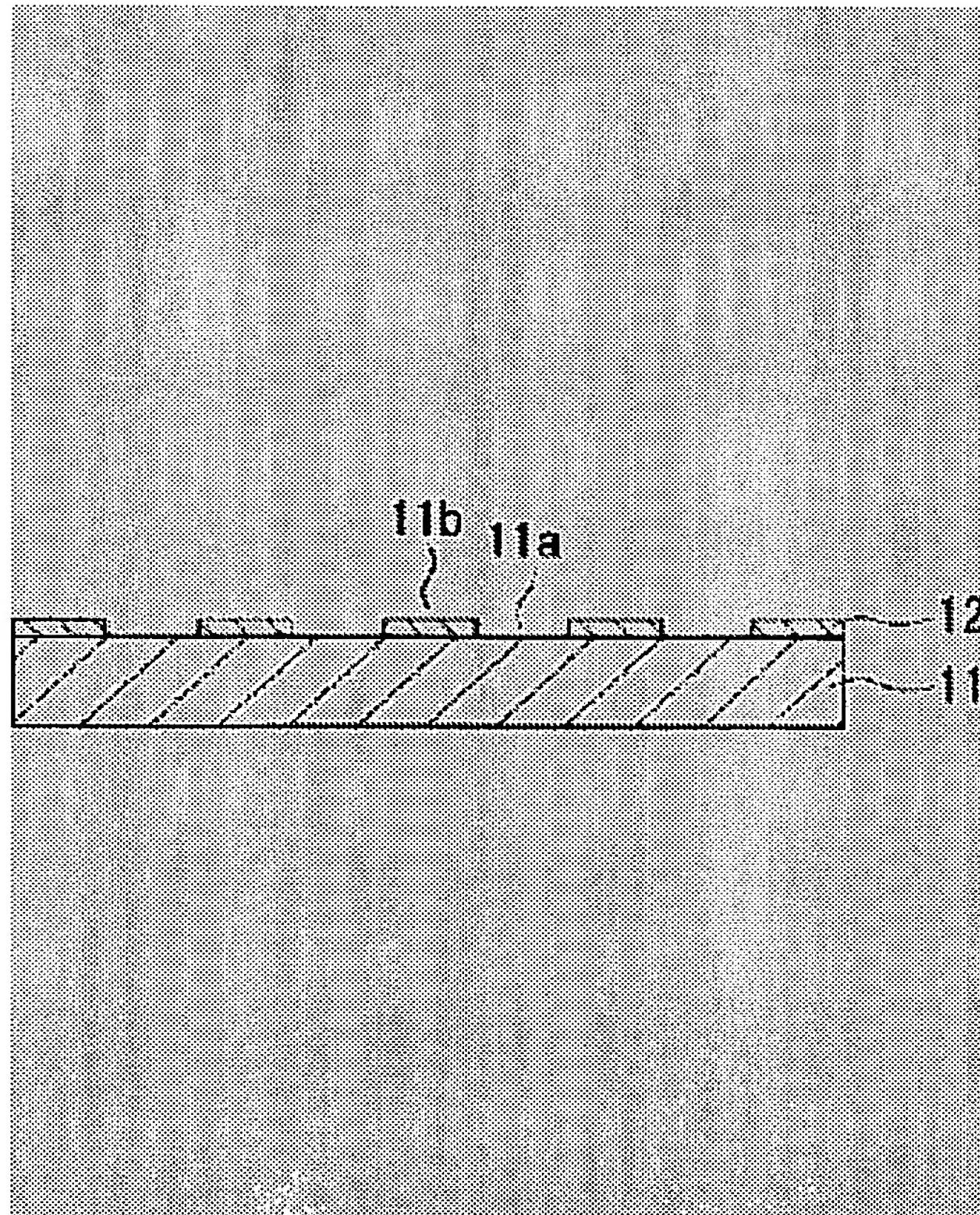
Patent number: JP2003149831
Publication date: 2003-05-21
Inventor: FURUSAWA MASAHIRO
Applicant: SEIKO EPSON CORP
Classification:
- international: G03F7/36; B41J2/01; H01L21/288; H01L21/3205;
H01L21/336; H01L29/786
- european:

Application number: JP20010344925 20011109
Priority number(s): JP20010344925 20011109

[Report a data error here](#)

Abstract of JP2003149831

PROBLEM TO BE SOLVED: To provide a liquid-repellent monolayer pattern forming method using no glass mask and excellent in pattern forming accuracy and reproducibility of position and to provide a pattern of a semiconductor, a metal or the like formed using the monolayer pattern, an electro-optic device manufactured using the formed pattern and an electronic machine with the electro-optic device. **SOLUTION:** A monolayer is formed on a substrate by bonding a silane compound having a hydrolyzable group and a carbon-containing group with liquid-repellent ends to the substrate, the top of the substrate is patternwise coated with an alkaline liquid by an ink jet process and the monolayer in the coated areas is removed by the hydrolytic action of the alkaline liquid to form a liquid-repellent monolayer pattern and a patterned lyophilic substrate surface. An electro-optic device is provided using the patterned substrate.



Data supplied from the **esp@cenet** database - Worldwide

BEST AVAILABLE COPY